

## Amendments to the Specification

**Page 9,        please replace the paragraph spanning lines 24-33 with the following rewritten paragraph:**

Also, the relation of the wavelength of light and the reflectivity in the low-reflective thin-film substrate was as shown by the curve A of Fig. 2, that is, the ~~maximum~~ minimum reflectivity in the visible light region (i.e., the wavelength region of from 400 to 700 nm ) was 0.05% ~~or lower~~ and the maximum reflectivity was 6.3% ~~or lower~~ when the wavelength was about 600 nm, which were very low. Also, in this case, the reflectivity was measured using a microspectroscope, OSP-SP 200, manufactured by Olympus Optical Company Limited using an aluminum thin film as a reference and did not include the reflectivity from a glass surface and so forth.

**Page 11,        please replace the paragraph spanning lines 22-28 with the following rewritten paragraph:**

Also, the relation of the wavelength of light and the reflectivity in the low-reflective thin-film substrate obtained is as shown in the curve C of Fig. 4, that is, the minimum reflectivity in the visible light region (i.e., the wavelength region of from 400 to 700 nm) was 0.05% ~~or lower~~ when the wavelength was 600 nm and the maximum reflectivity thereof was 4.7%, which were very low.

Example 3

**Page 12,        please replace the paragraph spanning line 28 to page 13, line 1 with the following rewritten paragraph:**

Also, the relation of the wavelength of light and the reflectivity in the low-reflective thin-film substrate obtained is as shown in the curve D of Fig. 4, that is, the minimum reflectivity in the visible light region (i.e., the wavelength region of from 400 to 700 nm) was 0.12% ~~or lower~~ when the wavelength was 610 nm and the maximum reflectivity thereof was 6.88%, which were very low.

Example 4

**Page 13,      please replace the paragraph spanning line 29 to page 14, line 1 with the following rewritten paragraph:**

Also, the relation of the wavelength of light and the reflectivity in the low-reflective thin-film substrate obtained is as shown in the curve E of Fig. 5, that is, the minimum reflectivity in the visible light region (i.e., the wavelength region of from 400 to 700 nm) was 0.11% ~~or lower~~ when the wavelength was 610 nm and the maximum reflectivity thereof was 6.06%, which were very low.

Example 5

**Page 15,      please replace the paragraph spanning lines 7-12 with the following rewritten paragraph:**

Also, the relation of the wavelength of light and the reflectivity in the low-reflective thin-film substrate was as shown by the curve F of Fig. 6, that is, the minimum reflectivity in the visible light region (i.e., the wavelength region of 400 to 700 nm) was 0.1% ~~or lower~~ and the average reflectivity in the visible light region was 2% or lower.

**Page 16,      please replace the paragraph spanning line 30 through page 17, line 2 with the following rewritten paragraph:**

Also, the relation of the wavelength of light and the reflectivity in the low-reflective thin-film substrate was as shown in the curve H of Fig. 8, that is, the minimum reflectivity thereof was 0.01% ~~or lower~~, the maximum reflectivity was 1.53%, and the average reflectivity was 0.24% ~~or lower~~ in the measured wavelength in the visible light region of from 400 to 700 nm, and thus the low-reflective thin-film substrate having a very low reflectivity was obtained.